

	Hits	Search Text	DBs
6	33	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (((additional or different or another or second) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or overlap\$4 or interconnect\$3)) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
7	0	((resist or photoresist) same (first or initial or interference or holograph\$4 or laser) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((second near18 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket)) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((second or dual) near26 (photoresist or resist or photosensitive) near16 (expos\$4 or mask or photomask)) and (laser same collimat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	26	((resist or photoresist) same (first or initial or interference or holograph\$4 or laser) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((second near18 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket)) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((second or dual) near26 (photoresist or resist or photosensitive) near16 (expos\$4 or mask or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB